

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

12. (Cancel)

13. (Cancel)

14. (Currently Amended) A surface treating apparatus according to claim ~~12~~ 21, wherein said vapor deposition controlling gas is hydrogen.

15. (Currently Amended) A surface treating apparatus according to claim ~~13~~ 21, wherein the molar ratio of said vapor deposition controlling gas to oxygen in at least ~~[[a]]~~ the space between said melting/evaporating source and said work within said treating chamber can be adjusted by the feed rate of said vapor-depositing material fed from said feed reel.

16. (Cancel)

21. (New): A surface treating apparatus comprising:  
a treating chamber connected to an evacuating system;

a melting / evaporating source for melting and evaporating a wire-shaped vapor-depositing material containing a vapor deposition controlling gas, disposed in the treating chamber;

a rotatable member, disposed in the treating chamber, and spaced above the melting/evaporating source, for retaining a work on which the vapor depositing material is deposited;  
and

a horizontally disposed feed reel of the wire-shaped vapor-depositing material containing the vapor deposition controlling gas to supply the wire-shaped vapor-depositing material containing the vapor deposition controlling gas to the melting / evaporating source, disposed in the treating chamber below the melting/evaporating source.